

10649645\_CLS  
Most Frequently Occurring Classifications of Patents Returned  
From A Search of 10649645 on July 28, 2004

Original Classifications

7 250/492.2  
7 250/492.22  
6 430/296  
4 250/491.1  
3 355/53  
2 356/500  
2 430/30  
2 430/5

Cross-Reference Classifications

7 250/398  
7 250/492.2  
6 250/492.22  
6 430/942  
5 430/296  
3 250/396R  
3 250/492.23  
3 250/492.3  
3 355/67  
3 430/5  
2 250/397  
2 250/491.1  
2 250/492.1  
2 430/426

Combined Classifications

14 250/492.2  
13 250/492.22  
11 430/296  
7 250/398  
6 250/491.1  
6 430/942  
5 430/5  
4 250/396R  
4 355/53  
3 250/397  
3 250/492.23  
3 250/492.3  
3 355/67  
2 250/310  
2 250/492.1  
2 356/500  
2 430/30

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2 430/426

10649645\_CLSTITLES

Titles of Most Frequently Occurring Classifications of Patents Returned

From A Search of 10649645 on July 28, 2004

14 250/492.2 (7 OR, 7 XR)  
 Class 250 : RADIANT ENERGY  
 250/492.1 IRRADIATION OF OBJECTS OR MATERIAL  
 250/492.2 .Irradiation of semiconductor devices

13 250/492.22 (7 OR, 6 XR)  
 Class 250 : RADIANT ENERGY  
 250/492.1 IRRADIATION OF OBJECTS OR MATERIAL  
 250/492.2 .Irradiation of semiconductor devices  
 250/492.22 ..Pattern control

11 430/296 (6 OR, 5 XR)  
 Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,  
 COMPOSITION, OR PRODUCT THEREOF  
 430/269 IMAGING AFFECTING PHYSICAL PROPERTY OF  
 RADIATION SENSITIVE MATERIAL, OR PRODUCING  
 NONPLANAR OR  
 PRINTING SURFACE - PROCESS, COMPOSITION, O  
 R PRODUCT  
 430/296 .Electron beam imaging

7 250/398 (0 OR, 7 XR)  
 Class 250 : RADIANT ENERGY  
 250/396R WITH CHARGED PARTICLE BEAM DEFLECTION OR  
 FOCUSSING  
 250/398 .With target means

6 250/491.1 (4 OR, 2 XR)  
 Class 250 : RADIANT ENERGY  
 250/491.1 MEANS TO ALIGN OR POSITION AN OBJECT RELATIVE  
 TO A SOURCE OR DETECTOR

6 430/942 (0 OR, 6 XR)  
 Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,  
 COMPOSITION, OR PRODUCT THEREOF  
 430/942 ELECTRON BEAM

5 430/5 (2 OR, 3 XR)  
 Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,  
 COMPOSITION, OR PRODUCT THEREOF  
 430/4 RADIATION MODIFYING PRODUCT OR PROCESS OF  
 MAKING  
 430/5 .Radiation mask

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- 4 250/396R (1 OR, 3 XR)  
Class 250 : RADIANT ENERGY  
250/396R WITH CHARGED PARTICLE BEAM DEFLECTION OR  
FOCUSSING
- 4 355/53 (3 OR, 1 XR)  
Class 355 : PHOTOCOPYING  
355/18 PROJECTION PRINTING AND COPYING CAMERAS  
355/53 .Step and repeat
- 3 250/397 (1 OR, 2 XR)  
Class 250 : RADIANT ENERGY  
250/396R WITH CHARGED PARTICLE BEAM DEFLECTION OR  
FOCUSSING  
250/397 .With detector
- 3 250/492.23 (0 OR, 3 XR)  
Class 250 : RADIANT ENERGY  
250/492.1 IRRADIATION OF OBJECTS OR MATERIAL  
250/492.2 .Irradiation of semiconductor devices  
250/492.23 ..Variable beam
- 3 250/492.3 (0 OR, 3 XR)  
Class 250 : RADIANT ENERGY  
250/492.1 IRRADIATION OF OBJECTS OR MATERIAL  
250/492.3 .Ion or electron beam irradiation
- 3 355/67 (0 OR, 3 XR)  
Class 355 : PHOTOCOPYING  
355/18 PROJECTION PRINTING AND COPYING CAMERAS  
355/67 .Illumination systems or details
- 2 250/310 (1 OR, 1 XR)  
Class 250 : RADIANT ENERGY  
250/306 INSPECTION OF SOLIDS OR LIQUIDS BY CHARGED  
PARTICLES  
250/310 .Electron probe type
- 2 250/492.1 (0 OR, 2 XR)  
Class 250 : RADIANT ENERGY  
250/492.1 IRRADIATION OF OBJECTS OR MATERIAL
- 2 356/500 (2 OR, 0 XR)  
Class 356 : OPTICS: MEASURING AND TESTING  
356/450 BY LIGHT INTERFERENCE (E.G., INTERFEROMETER)  
356/496 .For dimensional measurement  
356/498 ..Displacement or distance

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356/500 ...X-Y and/or Z table

2 430/30 (2 OR, 0 XR)  
Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,  
COMPOSITION, OR PRODUCT THEREOF  
430/30 INCLUDING CONTROL FEATURE RESPONSIVE TO A TEST  
OR MEASUREMENT

2 430/426 (0 OR, 2 XR)  
Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,  
COMPOSITION, OR PRODUCT THEREOF  
430/401 POST IMAGING PROCESSING  
430/423 .Treating with processing composition after  
imaging prior to developing  
430/426 ..Prehardening